

<b>Notice of References Cited</b>	Application/Control No. 10/658,372		Applicant(s)/Patent Under Reexamination SHOKI, TSUTOMU	
	Examiner John Ruggles		Art Unit 1756	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2001/0019803	09-2001	Mirkanimi, Paul B.	430/5
*	B	US-6,319,635	11-2001	Mirkarimi et al.	430/5
*	C	US-6,048,652	04-2000	Nguyen et al.	430/5
*	D	US-6,396,900	05-2002	Barbee et al.	378/84
*	E	US-2003/0152845	08-2003	Kumada et al.	430/5
*	F	US-6,596,465	07-2003	Mangat et al.	430/311
*	G	US-5,958,627	09-1999	Shoki, Tsutomu	430/5
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Levinson, Harry J., Principles of Lithography, 2001, SPIE --The International Society for Optical Engineering, Page 343
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.